

Supporting Information for

**An efficient Cu⁺ doped Gd-based fluoroaluminosilicate
scintillator glass for X-ray detector**

Guanlin He, Lianjie Li, Junyu Chen, Yujia Gong, Hai Guo*

Department of Physics, Zhejiang Normal University, Jinhua, 321004, China

* **Corresponding author:** Hai Guo, E-mail: ghh@zjnu.cn

A. Experimental

Preparation of glass samples:

A series of Cu⁺ doped glass scintillators was prepared by melt quenching method. Raw materials include SiO₂ (A.R., from Sinopharm Chemical Reagent Co., Ltd.), Al₂O₃ (A.R., from Sinopharm Chemical Reagent Co., Ltd.), SrF₂ (C.P., from Meryer Biochemical Technology Co., Ltd.), GdF₃ (99.99%, from A&C Rare Earth Materials Center), Cu₂O (99%, from Meryer Biochemical Technology Co., Ltd.) and aluminum powder (A.R., from Shanghai Zhanyun Chemical Co., Ltd.). First, the ingredients were thoroughly ground in an agate mortar for about 30 minutes. Then, the mixed powder was put into Al₂O₃ crucible and melted in air atmosphere at 1550 °C for 1 hour. The molten liquid was poured onto a copper plate preheated to 300 °C and pressed with another copper plate to obtain glass sample. The glass samples were annealed at 500 °C for 4 hours, and finally the samples were cut and polished to thickness of 2 mm for subsequent characterization.

Characterizations of structural, luminescent and scintillating properties:

The X-ray diffraction (XRD) patterns of Cu⁺ doped fluoroaluminosilicate glass were obtained by Rigaku MiniFlex/600 X-ray diffractometer (Tokyo, Japan). The Fourier transform infrared spectroscopy (FTIR) spectra of G-host and GCu3Al5.5 mixed with KBr powder at 1:10 ratio were obtained by using NEXUS 670 spectrophotometer (Massachusetts, USA). Transmittance spectra of 200-800 nm were measured by Hitachi U-3900 Ultraviolet-visible (UV-Vis) photometer (Tokyo, Japan). The photoluminescence excitation (PLE) spectra, photoluminescence (PL) spectra, internal quantum efficiency (IQE), external quantum efficiency (EQE), absorption efficiency (Abs) and fluorescence attenuation curves were obtained by Edinburgh FS5 fluorescence spectrometer (Livingston, UK) using xenon lamp as pump source. The refractive index (n) at 589 nm was measured by GI-RDB digital refractometer (Nanjing, China). The density (ρ) was measured according to Archimedes' principle by using deionized water as an immersion liquid. XEL spectra were acquired using the Zolix OmniFluo960 XEL spectrometer (Beijing, China) with X-ray tubes, and all samples

were compared with commercial $\text{Bi}_4\text{Ge}_3\text{O}_{12}$ (BGO) scintillator (2 mm). The BGO crystal was purchased from Shanghai Institute of Ceramics, Chinese Academy of Sciences, which is one of best quality suppliers of BGO crystal. The specific parameters were listed in following Table S1. X-ray images were taken with a Canon EOS 600D camera, and the $\text{GCu}_3\text{Al}_5.5$ glass was polished to 0.5 mm thickness for X-ray imaging. The XPS spectra were obtained by Thermo Scientific K-Alpha (Waltham, U.S.).

Table S1 Parameters of BGO crystal from Shanghai Institute of Ceramics, Chinese Academy of Sciences.

| Parameter | Value |
|--------------------------------------|-----------|
| Density (g/cm^3) | 7.13 |
| Radiation length (cm) | 1.12 |
| Decay constant (ns) | 300 |
| Emission peak (nm) | 480 |
| Light output (ph/MeV) | 8000-9000 |
| Melting point ($^{\circ}\text{C}$) | 1050 |
| Hardness (Mho) | 5 |
| Refractive Index | 2.15 |
| Hygroscopicity | none |
| Cleavage | none |

B. The energy gap (E_g) between conduction band and valence band of the G-host

The Relationship between α^2 and $h\nu$ of G-host sample is displayed in Fig. S1. E_g of G-host is calculated according to the following formula, ¹

$$\alpha = B(h\nu - E_g)^{\frac{1}{2}} \quad (\text{S1})$$

where α stands for absorption coefficient, B represents constant, E_g is bandgap and $h\nu$ is photon energy, respectively.

The α is derived by converting transmittance data through $T = I/I_0$ and $I = I_0e^{-\alpha d}$, where T , I , I_0 and d stand for transmittance, transmitted intensity, incident intensity and thickness of glass. E_g value of G-host is calculated to be 3.95 eV.

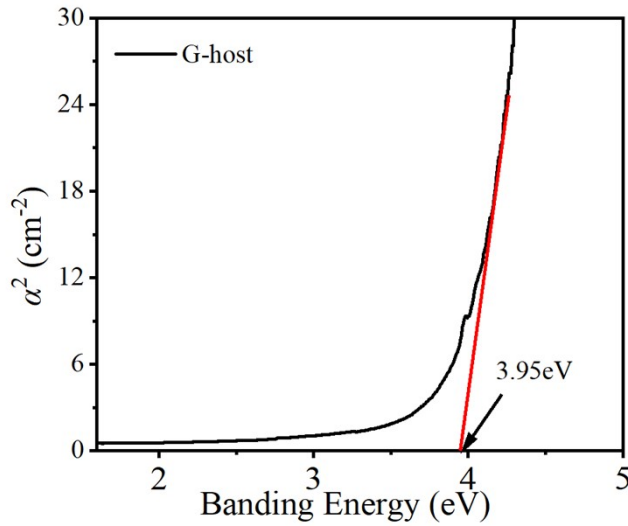


Fig. S1 Relationship between α^2 and $h\nu$ of G-host sample with thickness of 2 mm.

C. XPS spectra of GCu3Al5 and GCu3Al5.5 samples

To further demonstrate the reduction process occurred in Al-doped samples, Fig. S2(a) and Fig. S2(b) show the high-resolution XPS spectra of Cu 2p of GCu3Al5 and GCu3Al5.5 samples, respectively. Four sharp peaks can be observed. The peaks at 932.6, 952.1, 933.6 and 953.8 eV are corresponded to $^2P_{3/2}$ orbit of Cu^+ , $^2P_{1/2}$ orbit of Cu^+ , $^2P_{3/2}$ orbit of Cu^{2+} and $^2P_{1/2}$ orbit of Cu^{2+} , respectively.²⁻⁵ When the content of Al increases, the integral area of Cu^+ increases significantly and that of Cu^{2+} decreases rapidly. Therefore, the reduction process from Cu^{2+} to Cu^+ has been clearly proved.

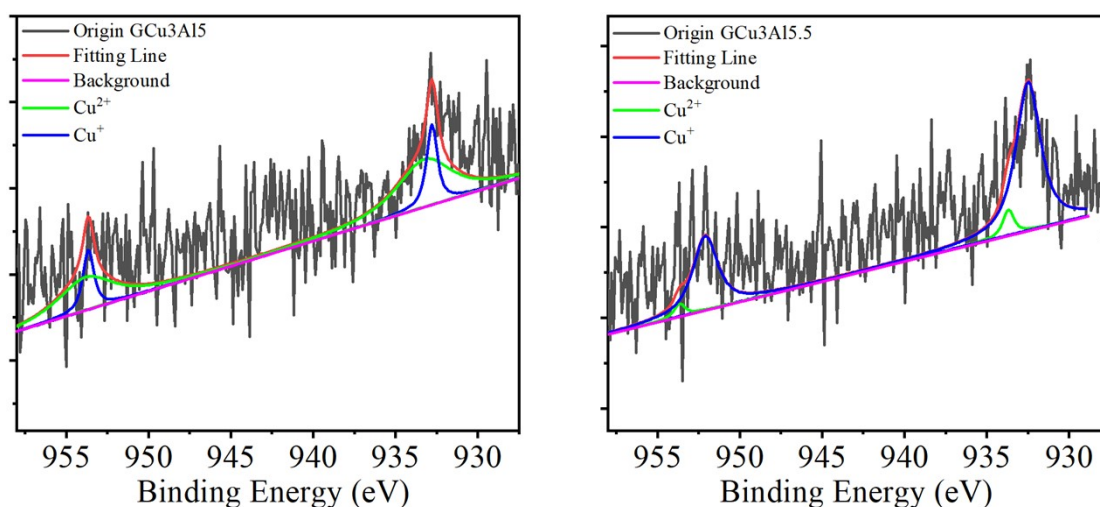


Fig. S2 High-resolution XPS spectra of Cu 2p of (a) GCu3Al5 and (b) GCu3Al5.5 samples.

D. IQE, EQE and Abs of GCu3Al5.5 sample

The IQE, EQE and Abs were tested under 291 nm and 273 nm excitation, as shown in Fig. S3(a) and S3(b), respectively. The IQE, EQE, and Abs can be calculated using the following equations,^{6,7}

$$\text{IQE} = \frac{\int L_{\text{sample}}}{\int E_{\text{reference}} - \int E_{\text{sample}}} \quad (\text{S2})$$

$$\text{EQE} = \frac{\int L_{\text{sample}}}{\int E_{\text{reference}}} \quad (\text{S3})$$

$$\text{Abs} = \frac{\text{EQE}}{\text{IQE}} \quad (\text{S4})$$

where L_{sample} is the PL spectra of sample; $E_{\text{reference}}$ and E_{sample} stand for the spectra of excitation light with BaSO₄ (as a reference) and sample, respectively; and the spectra were collected using an integrating sphere.

The IQE value of GCu3Al5.5 is 63.0% excited by 291 nm and 76.2% excited by 273 nm. The EQE value of GCu3Al5.5 is 55.3% excited by 291 nm and 66.7% excited by 273 nm. The Abs value of GCu3Al5.5 is 87.7% excited by 291 nm and 87.5% excited by 273 nm. The GCu3Al5.5 sample has high IQE, EQE and Abs, which symbolize that it might be a candidate for scintillator materials.

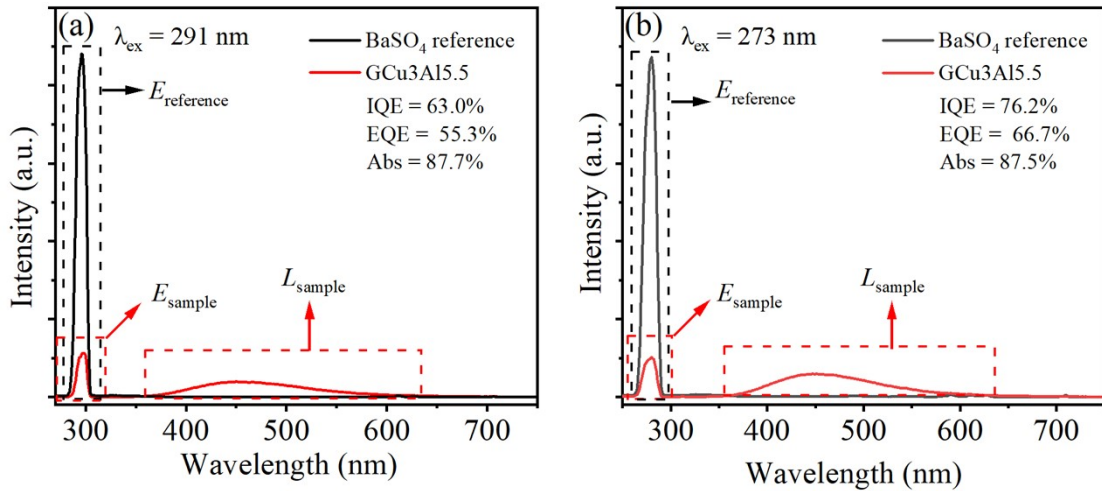


Fig. S3 (a) PL spectra ($\lambda_{\text{ex}} = 291 \text{ nm}$) and (b) PL spectra ($\lambda_{\text{ex}} = 273 \text{ nm}$) for measurement of IQE, EQE and Abs value by using an integrating sphere for GCu3Al5.5 sample.

E. Effect of GdF₃ concentration on XEL intensity

The effect of GdF₃ concentration on XEL intensity was investigated. The nominal compositions of samples are exhibited in Table S2 and their corresponding XEL spectra are shown in Fig. S4. With the increase of Gd³⁺ concentration, the XEL intensity of glass samples first increase and then decrease. The optimal GdF₃ content is 7 mol%. Therefore, in this work, content of GdF₃ is fixed at 7 mol%.

Table S2 The nominal concentrations of SiO₂, Al₂O₃, SrF₂, GdF₃, Cu₂O and Al in each glass sample (in mol ratio).

| Sample | SiO ₂ | Al ₂ O ₃ | SrF ₂ | GdF ₃ | Cu ₂ O | Al |
|---------------|------------------|--------------------------------|------------------|------------------|-------------------|------|
| GCu3Al5.5-Gd5 | 70 | 7 | 16 | 5 | 0.15 | 0.55 |
| GCu5Al5.5-Gd7 | 70 | 7 | 16 | 7 | 0.15 | 0.55 |
| GCu3Al5.5-Gd9 | 70 | 7 | 16 | 9 | 0.15 | 0.55 |

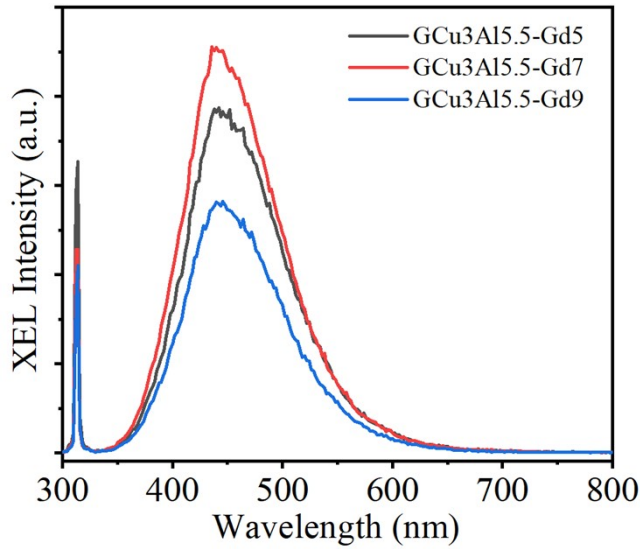


Fig. S4 XEL spectra of GCu3Al5.5-GdZ (Z = 5, 7, 9) samples.

F. Refractive index (n), density (ρ) and effective atomic number (Z_{eff}) of GCuXAlY samples

Refractive index (n), density (ρ) and effective atomic number (Z_{eff}) are fundamental and important parameters for glass scintillation. Z_{eff} values are estimated by using the following formula,⁸

$$Z_{eff} = \sqrt[2.94]{f_1(Z_1)^{2.94} + f_2(Z_2)^{2.94} + \dots + f_i(Z_i)^{2.94}} \quad (S5)$$

where f_i is fraction of total number of electrons associated with each element, and Z_i is atomic number of each element. These parameters of GCuXAlY samples are listed in Table S3.

Table S3 The refractive index (n) at 589 nm, density (ρ) and effective atomic number (Z_{eff}) of GCuXAlY samples.

| Sample | n | ρ (g/cm ³) | Z_{eff} |
|-----------|-------|-----------------------------|-----------|
| GCu1Al5.5 | 1.497 | 3.30 | 20.87 |
| GCu2Al5.5 | 1.522 | 3.31 | 20.87 |
| GCu3Al5.5 | 1.577 | 3.44 | 20.87 |
| GCu4Al5.5 | 1.550 | 3.51 | 20.87 |
| GCu5Al5.5 | 1.520 | 3.62 | 20.88 |
| GCu6Al5.5 | 1.516 | 3.64 | 20.88 |

G. Details of irradiation properties of GCu3Al5.5

The XEL spectra of GCu3Al5.5 are recorded every five minutes during 0-120 min. Fig. S5(a) shows these spectra. The XEL intensity of GCu3Al5.5 increases continuously in the first 40 minutes, then remains stable. And the final XEL intensity of GCu3Al5.5 is about 150% of its initial XEL intensity. Fig. S5(b) exhibits the transmittance spectra of GCu3Al5.5 sample before and after irradiation. After 120 min of irradiation, GCu3Al5.5 sample still maintain a high transmittance, indicating that GCu3Al5.5 sample has excellent radiation resistance capacity.

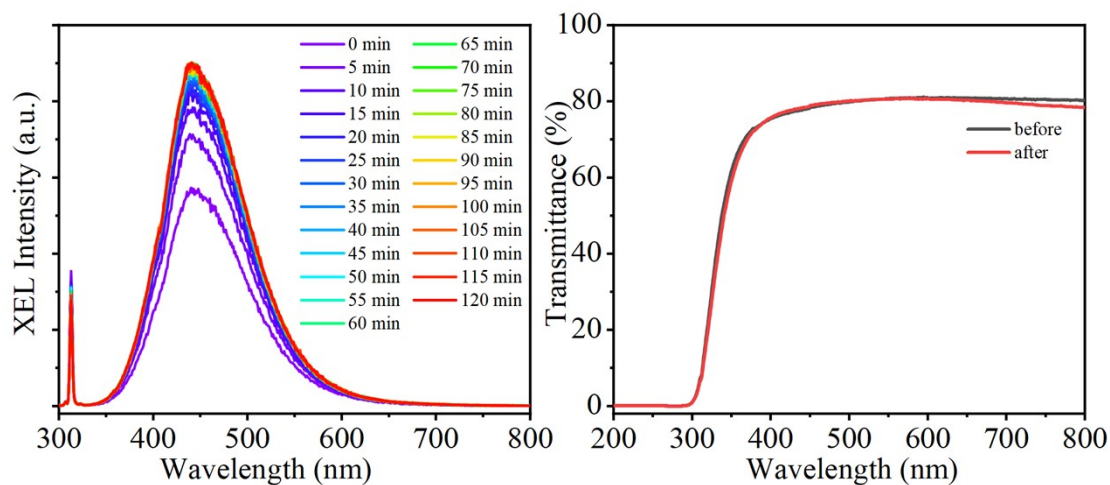


Fig. S5(a) XEL spectra of GCu3Al5.5 sample under continuous X-ray irradiation for 0- 120 min. (b) Transmittance spectra of GCu3Al5.5 sample before and after irradiation.

H. Schematic diagram of equipment for X-ray imaging

To assess the X-ray imaging performance of GCu₃Al_{5.5}, X-ray images of a chip, a capsule containing a nail a capsule containing a spring and standard X-ray resolution test pattern plate were taken by home-made equipment for X-ray imaging, as shown in Fig. S6.

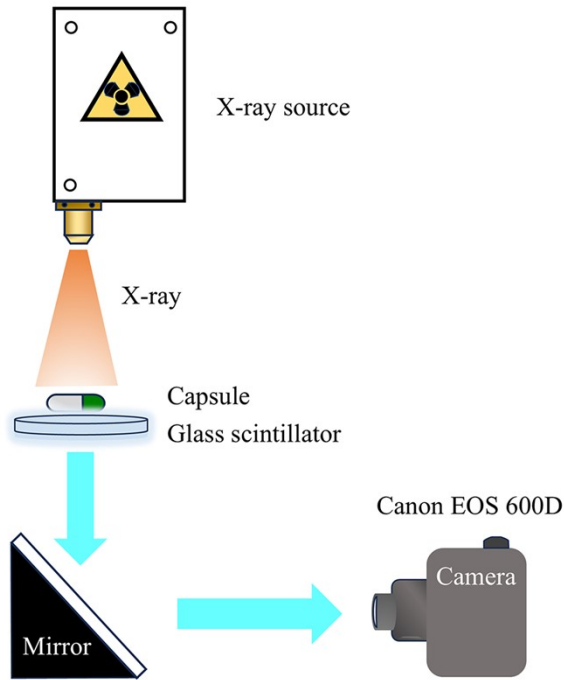


Fig. S6 Schematic diagram of the home-made equipment for X-ray imaging.

Reference

1. S. Y. Z. Chen, L. J. Li, J. Y. Chen, S. u. Xu, W. J. Huang, Z. X. Wen, T. M. Jiang and H. Guo, *J. Mater. Chem. C*, 2023, **11**, 2389-2396.
2. T. Ghodselahi, M. A. Vesaghi, A. Shafiekhani, A. Baghizadeh and M. Lameii, *Appl. Surf. Sci.*, 2008, **255**, 2730-2734.
3. J. A. Torres-Ochoa, D. Cabrera-German, O. Cortazar-Martinez, M. Bravo-Sanchez, G. Gomez-Sosa and A. Herrera-Gomez, *Appl. Surf. Sci.*, 2023, **622**, 156960.
4. S. Natesakhawat, J. W. Lekse, J. P. Baltrus, P. R. Ohodnicki, Jr., B. H. Howard, X. Deng and C. Matranga, *Acs Catal.*, 2012, **2**, 1667-1676.
5. D. V. Sivkov, O. V. Petrova, S. V. Nekipelov, A. S. Vinogradov, R. N. Skandakov, S. I. Isaenko, A. M. Ob'edkov, B. S. Kaverin, I. V. Vilkov, R. I. Korolev and V. N. Sivkov, *Nanomaterials*, 2021, **11**, 2993.
6. S. Y. Z. Chen, W. N. Zhang, L. M. Teng, J. Chen, X. Y. Sun, H. Guo and X. S. Qiao, *J. Eur. Ceram. Soc.*, 2021, **41**, 6722-6728.
7. S. Y. Z. Chen, Y. J. Gong, W. J. Huang, Z. X. Wen, L. J. Li, G. A. Ashraf, L. Lei, J. K. Cao and H. Guo, *J. Mater. Chem. C*, 2022, **10**, 10382-10388.
8. M. P. Singh, B. S. Sandhu and B. Singh, *Nucl. Instrum. Meth. A.*, 2007, **580**, 50-53.